

## Example Final Exam for ELEC 321

### Problem #1 (10%)

A cubic unit-cell is defined in terms of the following placement of atoms on a cube of edge-length  $a$ :

- 4 atoms positioned  $a/2$  up each of the vertical edges of the cube
- 2 atoms in the middle of the top and bottom surfaces.

- (a) This unit cell explains one of the standard cubic unit cell which were named in class. Which one is it? **(5 points)**
- (b) How many atoms are there per unit cell? **(5 points)**

### Problem #2 (15%)

For the step potential function shown in Fig. P2, assume that particle energy  $E > V_0$  and that the particle is incident from the  $+x$  direction traveling in the  $-x$  direction.

- (a) Write the wave solutions for each region **(5 points)**
- (b) Derive expressions for the transmission and reflection coefficients. **(10 points)**

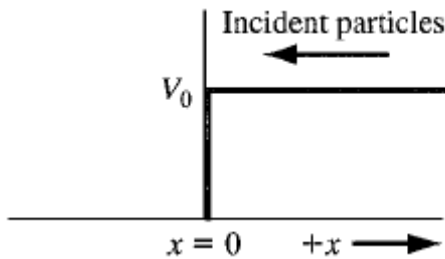


Fig. P2

### Problem #3 (15%)

The Fermi energy level for copper at  $T = 300$  K is 7.0 eV. The electrons in copper follow the Fermi-Dirac distribution function.

- (a) Find the probability of an energy level at 7.15 eV being occupied by an electron. **(5 points)**
- (b) Find the probability of an energy level at 6.85 eV being occupied by an electron. **(5 points)**
- (c) Determine the probability of an energy level at  $E = E_F$  being occupied at  $T = 300$  K and at 1000 K. **(5 points)**

### Problem #4 (15%)

Consider Si sample at  $T = 300$  K with a donor concentration three times the acceptor concentration.

- (a) If the probability of finding an electron at the bottom of conduction band is  $10^{-5}$  calculate the electron and hole concentration. **(5 points)**

- (b) Calculate the acceptor and donor concentration assuming complete ionization. **(5 points)**  
 (c) Calculate the electron and hole concentration at  $T = 500$  K. **(5 points)**

**Problem #5 (10%)**

At  $300^\circ\text{K}$ , in an n-type silicon slab of  $1\mu\text{m}$  thickness, the donor concentration is changing exponentially from the surface down according to

$$N_d(x,y) = 10^{17} \exp\left[-\frac{(x-0.25)^2}{0.1}\right] \text{ cm}^{-3}; \text{ x is in micrometers.}$$

$x$  is the coordinate normal to the surface ( $x=0$  marks the surface) and  $y$  is coordinate parallel to the surface.

- (a) What is the maximum value of internally-induced electric-field perpendicular to the surface? Please pay very careful attention to the units!  
 (b) What is the maximum value of internally-induced electric field in the horizontal direction? Please pay very careful attention to the units!

**Problem #6 (20%)**

The semiconductor is a homogeneous, p-type material in thermal equilibrium for  $t \leq 0$ . The excess minority carrier lifetime is  $\tau_{n0} = 10^{-6} \text{ s}$ . At  $t = 0$ , an external source is turned on which produces excess carriers uniformly at rate of  $g' = 10^{20} \text{ cm}^{-3} \text{ s}^{-1}$ . At  $t = 2 \times 10^{-6} \text{ s}$ , the external source is turned off.

- (a) Derive the expression for the excess-electron concentration as a function of time for  $0 \leq t \leq \infty$ . **(7 points)**  
 (b) Determine the value of excess electron concentration at (i)  $t = 0$ , (ii)  $t = 2 \times 10^{-6} \text{ s}$ , (iii)  $t = 3 \times 10^{-6} \text{ s}$  and (iv)  $t = \infty$ . **(8 points)**  
 (c) Plot the excess electron concentration as a function of time. **(5 points)**

**Problem #7 (15%)**

Consider a GaAs p-n junction uniformly doped on either side of the metallurgical junction.  $T$  is  $300 \text{ K}$ . At zero bias, only 20 percent of the total space charge region is to be in the “p” region. The built-in potential is  $V_{bi} = 1.2 \text{ V}$ . For zero bias determine  $N_a$ ,  $N_d$ ,  $x_n$ ,  $x_p$ ,  $W$ , and  $E_{\text{max}}$ . Relative permittivity of GaAs is 13.1.